

# Glass Substrate and Media Cleaning Solutions

*Perform superior cleaning and protect glass substrates from undesirable etch*

Our hard disk drive (HDD) cleans are designed to be used after slurry polishing. They perform superior cleaning while protecting glass substrates from undesirable etch. The formulation is designed to remove colloidal silica, ceria, slurry additives, suspension agents, organic residues, and inorganic sub-micron particulates left or embedded on glass disks during polishing. Our cleaning solutions significantly reduce surface ion contamination and remove, suspend, and completely disperse contaminants. Cleaners are formulated to be used at ambient temperatures and are exceptionally free-rinsing.



## APPLICATIONS

- Optics glass
- Electronics glass
- HDD glass
- Post-CMP clean lines (immersion, brush, spray, ultrasonic, megasonic)

## FEATURES & BENEFITS

<b>High performance surfactant technology</b>	Allows high dispersion and free-rinsing
	Suspends and removes difficult-to-clean organic films, organic particulates, and inorganic particulates
	Reduces friction allowing easy use in brush processes
<b>Cleans effectively at ambient temperature</b>	Minimizes dry-down residues
<b>Well buffered cleaning solution</b>	Has high impact at a variety of concentrations (generally 1-10%)

## SPECIFICATIONS

Product family	Key features
GCL 129 series	<ul style="list-style-type: none"><li>• Highly alkaline substrate cleaners used in post-polish</li><li>• Highly efficient surfactant package for wettability</li><li>• Surfactants compatible with PVA brushes</li><li>• Effective dispersants to minimize silica redeposition on glass</li></ul>
GCL 31 series	<ul style="list-style-type: none"><li>• Sulfuric-based acidic cleaners used in post-polish</li><li>• Surfactants compatible with PVA brushes</li><li>• Additives to solubilize ceria</li><li>• Low foaming surfactants: applied in megasonic, ultrasonic, and spray</li><li>• Uniform glass-etch capabilities</li></ul>
GCL P1 series	<ul style="list-style-type: none"><li>• Acidic, two-part cleaner used in post-ID/OD grind and polish</li><li>• Additives to efficiently digest ceria particles</li><li>• Surfactants to minimize ceria redeposition</li><li>• Additives to hold ceria in solution</li><li>• Low foaming surfactants: applied in megasonic, ultrasonic, and spray</li><li>• Uniform glass-etch capabilities</li></ul>
GCL 131 series	<ul style="list-style-type: none"><li>• Alkaline media cleaners</li><li>• High purity chelants to minimize transition metal oxides</li><li>• Additives to minimize surface roughness</li><li>• High rinsing surfactant package to enable IPA drying process</li><li>• Dispersants to minimize glass particle adhesion</li></ul>

### FOR MORE INFORMATION

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